

Title (en)  
PLASMA DISCHARGE APPARATUS AND METHOD OF USING THE SAME

Title (de)  
PLASMAENTLADUNGSVORRICHTUNG UND VERFAHREN ZUR VERWENDUNG DAVON

Title (fr)  
APPAREIL À DÉCHARGE DE PLASMA ET SON PROCÉDÉ D'UTILISATION

Publication  
**EP 3849284 A1 20210714 (EN)**

Application  
**EP 20151015 A 20200109**

Priority  
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Abstract (en)  
The present invention relates to a plasma discharge apparatus comprising a first electrode structure comprising a plurality of trigger points; a second electrode structure; and a voltage source connected to the first and/or second electrode structures, the voltage source being configured to create a potential difference between the first and second electrode structures such that at least one electrical discharge occurs in a discharge region, wherein each electrical discharge has a discharge path with a first end contacting the first electrode structure and a second end contacting the second electrode structure. The apparatus further comprises a means for exerting force on the at least one electrical discharge, the means being configured to compel the first end of the discharge path to move along the first electrode structure. Each trigger point is a portion of the first electrode structure which has a smaller gap distance to the second electrode structure than adjacent portions of the first electrode structure, such that the at least one electrical discharge is initiated at one of the plurality of trigger points.

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Citation (applicant)  
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